## **Supplementary Material**

## Insights into interactions of chlorine-based cleaning products with indoor relevant surfaces

Michael R. Alves<sup>A</sup>, Cholaphan Deeleepojananan<sup>A</sup>, Victor W. Or<sup>A</sup>, Izaac Sit<sup>B</sup> and Vicki H. Grassian<sup>A,\*</sup>

<sup>A</sup>Department of Chemistry and Biochemistry, University of California San Diego, La Jolla, CA 92093, USA

<sup>B</sup>Department of Nanoengineering, University of California San Diego, La Jolla, CA 92093, USA

\*Correspondence to: Email: <u>vhgrassian@ucsd.edu</u>

Supplemental Information:

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Cleaning Products with Indoor Relevant Surfaces

Michael R. Alves, Cholaphan Deeleepojananan, Victor W. Or, Izaac Sit and Vicki H. Grassian

<sup>1</sup>Department of Chemistry and Biochemistry, University of California San Diego, La Jolla, CA 92093



Figure S1. (a) XPS of SiO<sub>2</sub> sample exposed to gas-phase HOCl under dried conditions and then analyzed several weeks later with XPS. There are no peaks evident in the Cl 2p region. (b) XPS of TiO<sub>2</sub> sample exposed to gas-phase HOCl under dried conditions and then analyzed several weeks later with XPS. Peaks due to chloride Cl  $2p_{3/2}$  and  $2p_{1/2}$  near 198 and 200 eV, respectively.